



Inventor: Harry Rosenberg

Title: Tantalum Sputtering Target and Method of Manufacture

Assignee: Micron Technology, Inc.

Docket No. 34593-CON1

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#9
D. Scott
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INFORMATION DISCLOSURE STATEMENT

PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation application of co-pending application Serial No. 09/717,476, filed November 20, 2000. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. § 1.98(d) and MPEP § 609(2).

Citation of these references is respectfully requested.

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Respectfully submitted,

Dated: 03 Feb 2003

By: 

James E. Lake
Reg. No. 44,854